

AP20 Rec'd PCT/PTO 09 AUG 2006

SHIGA7.053APC

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Ogata et al.
Appl. No. : U.S. National Phase of
PCT/JP2005/000660
Filed : Herewith
For : POLYMER COMPOUND,
PHOTORESIST COMPOSITION
INCLUDING THE POLYMER
COMPOUND, AND RESIST
PATTERN FORMATION
METHOD
Examiner : Unassigned
Group Art Unit : Unknown

CERTIFICATE OF MAILING

I hereby certify that this correspondence and all marked attachments are being deposited with the United States Postal Service as first-class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on

August 9, 2006

(Date)

Neil S. Bartfeld, Ph.D., Reg. No. 79,901

PRELIMINARY AMENDMENT**Mail Stop PCT**

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Prior to examination of the above-referenced application, please enter the following amendments:

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims begin on page 3 of this paper.

Remarks begin on page 5 of this paper.